	Application No.	Applicant(s)
No. 45 E. A.H L.194	09/945,247	HIGASHI ET AL.
Notice of Allowability	Examiner	Art Unit
	Ida M Soward	2822
The MAILING DATE of this communication appearance All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIOF the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this apport or other appropriate communication (GHTS. This application is subject to	plication. If not included will be mailed in due course. THIS
1. $\boxtimes$ This communication is responsive to <u>the Applicants' remar</u>	ks filed November 23, 2004.	
2. The allowed claim(s) is/are <u>1-16</u> .		
3. $\boxtimes$ The drawings filed on <u>8-31-01</u> are accepted by the Examin	er.	
<ul> <li>4.  Acknowledgment is made of a claim for foreign priority una)  All b)  Some* c)  None of the:</li> <li>1.  Certified copies of the priority documents have</li> <li>2.  Certified copies of the priority documents have</li> <li>3.  Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)).</li> <li>* Certified copies not received:</li> </ul> Applicant has THREE MONTHS FROM THE "MAILING DATE"	been received. been received in Application No cuments have been received in this of this communication to file a reply	national stage application from the
noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give	itted. Note the attached EXAMINER	
6. ☐ CORRECTED DRAWINGS (as "replacement sheets") mus  (a) ☐ including changes required by the Notice of Draftspers  1) ☐ hereto or 2) ☐ to Paper No./Mail Date  (b) ☐ including changes required by the attached Examiner's Paper No./Mail Date  Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the sheet. Replacement sheet(s) should be labeled as such in the deposate of the same of the same of the sheet.	st be submitted. son's Patent Drawing Review (PTO- s Amendment / Comment or in the C .84(c)) should be written on the drawin he header according to 37 CFR 1.121(c) sit of BIOLOGICAL MATERIAL n	948) attached  Office action of the back) of d).  nust be submitted. Note the
and the Examiner's comment regarding INEQUINERY	TOR THE BEFOST OF BIOLOGICA	AL WATERIAL.
Attachment(s)		
<ol> <li>Notice of References Cited (PTO-892)</li> <li>D Notice of Draftperson's Patent Drawing Review (PTO-948)</li> </ol>	_	ratent Application (PTO-152)
	6.	
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date</li> </ol>	8), 7. X Examiner's Amenda	nent/Comment
4.   Examiner's Comment Regarding Requirement for Deposit		ent of Reasons for Allowance
of Biological Material	9.  Other	hn-
	्र - 	AMIR ZARADIAN SORY PATENT EXPANSER MOLOGY CENTER

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## **DETAILED ACTION**

This Office Action is in response to the Applicants' remarks filed November 23, 2004.

## **EXAMINER'S AMENDMENT**

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Gregory G. Schivley on January 26, 2005.

The preambles in claims 15 and 16 of the application has been amended as follows:

- 15. A method for the fabrication of an electronic apparatus comprising: forming a semiconductor layer serving as an active layer on a substrate; setting the substrate temperature at no higher than 100°C and forming a gate insulating film on said semiconductor layer, such that interface level density between the semiconductor layer and the gate insulating film is no greater than 10<sup>11</sup>cm<sup>-2</sup>eV<sup>-1</sup>, and heat treating said gate insulating film in an atmosphere containing water.
  - 16. A method for the fabrication of an electronic apparatus comprising: forming a semiconductor layer serving as an active layer on a substrate;

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setting the substrate temperature at no higher than 100°C and forming a firststage gate insulating film on said semiconductor layer, such that interface level density
between the semiconductor layer and the gate insulating film is no greater than 10<sup>11</sup>cm<sup>-2</sup>eV<sup>-1</sup>; and

setting said substrate temperature at no less than 100°C and forming a secondstage gate insulating film.

## Allowable Subject Matter

Claims 1-16 are allowed.

## Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

The following patents are cited to further show the state of the art with respect to a method for the fabrication of a field-effect transistor:

Kunikiyo (6,096,641)

Negishi et al. (5,498,557)

Yamazaki et al. (5,627,084)

Yamanaka et al. (US 6,653,212 B1).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ida M Soward whose telephone number is 571-272-1845. The examiner can normally be reached on Monday - Thursday, 6:30 am to 5:00 pm.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Amir Zarabian can be reached on 571-272-1852. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

IMS January 18, 2005

AMER ZARABIAN
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2807